

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT



Group Art Unit: 1756

Examiner: S. Mohamedulla

#1461B  
10/24/01

**PETITION FOR EXTENSION OF TIME**

Assistant Commissioner for Patents

Washington, D.C. 20231

Sir:

The following extension of time is requested to respond to Office Action dated June 19, 2001:

one month to October 19, 2001; the extension fee is:

\$55.00 (215)  \$110.00 (115).

The shortened statutory period has been reset by an Advisory Action dated

An extension fee in the amount of \$ 110.00 is enclosed.

Charge \$ \_\_\_\_\_ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

10/19/2001 HROCHA1 00000097 09320946

02 FC:115

110.00 OP

Respectfully submitted,

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Date: October 18, 2001

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